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<p>(21) International Application Number: PCT/GB99/04141 (22) International Filing Date: 14 December 1999 (14.12.99) (30) Priority Data: 9827480.6 15 December 1998 (15.12.98) GB (71) Applicant (for all designated States except US): THE UNIVERSITY OF YORK [GB/GB]; Heslington Hall, York YO1 5DD (GB). (72) Inventors; and (75) Inventors/Applicants (for US only): DENECKE, Jurgen [DE/GB]; Leeds Institute for Plant Biotechnology and Agriculture, University of Leeds, Leeds LS2 9JT (GB). JELITTO, Edith [NL/AT]; Kollersteig, Flat 1, A-3400 Klosterneuberg (AT). (74) Agent: HARRISON GODDARD FOOTE; Belmont House, 20 Wood Lane, Leeds LS6 2AE (GB).</p>	<p>(81) Designated States: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG).</p> <p>Published With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</p>	

(54) Title: PLANT-PATHOGEN RESISTANCE

(57) Abstract

The present invention provides a method of reducing the period within which a plant's natural defence mechanism responds to attack by a plant pathogen, the method comprising causing the plant to maintain in at least a part of the plant a level of BiP, or a homologue thereof, which is greater than the endogenous level for said plant in non-stressful conditions. The invention also provides for a modified plant produced by the method of the invention.

